

L Number	Hits	Search Text	DB	Time stamp
1	818	438/264	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:08
2	137	257/46	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:24
3	58971	method adj producing.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:09
4	10	(method adj producing.ti.) adj oxidation.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:10
6	175	"capacitive electrode".ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:37
11	13	"capacitive electrode structure"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:13
13	6	"capacitive electrode structure" and semiconductor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:13
14	1	("capacitive electrode structure" and semiconductor) and oxidation	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:14
15	2088	(semiconductor adj substrate) adj5 oxidation	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:31
16	1	((semiconductor adj substrate) adj5 oxidation) adj5 "metal oxide layer"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:16
17	1	((semiconductor adj substrate) adj5 oxidation) same "metal oxide layer"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:16
18	32	((semiconductor adj substrate) adj5 oxidation) same "metal oxide"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:16
21	10	((semiconductor adj substrate) adj5 oxidation) same "metal oxide") same "conductive"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:17

8	11	"capacitive electrode".ti. and "method".ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:18
10	7	"capacitive electrode".ti. and dram.ti.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:18
23	1	((((semiconductor adj substrate) adj5 oxidation) same "metal oxide") same "conductive") and tungsten	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:20
25	1	((semiconductor adj substrate) adj5 oxidation) and "electrical conductive"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:22
26	22	"metal oxide layer" and "electrical conductive"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:23
28	1	("metal oxide layer" and "electrical conductive") and capacitor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:23
30	1	((("metal oxide layer" and "electrical conductive") and semiconductor) and tungsten	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:23
29	7	("metal oxide layer" and "electrical conductive") and semiconductor	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:24
32	116	((semiconductor adj substrate) adj5 oxidation) same ("metal oxide layer" or mos)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:26
34	2	((((semiconductor adj substrate) adj5 oxidation) same ("metal oxide layer" or mos)) same (conductive or conductor)) and tungsten	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:26
33	15	((semiconductor adj substrate) adj5 oxidation) same ("metal oxide layer" or mos)) same (conductive or conductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:30
35	3142	(semiconductor adj substrate) near5 oxidation	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:32
36	2	((semiconductor adj substrate) near5 oxidation) near5 "metal oxide"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:34
37	47	((semiconductor adj substrate) near5 oxidation) same "metal oxide"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:35

38	9	((semiconductor adj substrate) near5 oxidation) same "metal oxide") same electrode	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:35
39	1	((semiconductor adj substrate) near5 oxidation) same "metal oxide") same electrode) same conductive	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:35
40	1	((semiconductor adj substrate) near5 oxidation) same "metal oxide") same electrode) same (conductive of conductor)	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:36
41	977	"capacitive electrode"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:38
42	5	((semiconductor adj substrate) adj5 oxidation) and "capacitive electrode"	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:40
43	1	krasemann-anke.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:40
44	0	krasemann-anke-\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:40
45	1	pompl-thomas.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:41
46	0	pompl-thomas-\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:41
47	37	schrems-martin.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:41
48	3	schrems-martin-\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:41
49	0	wurzer-helmut-\$.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:41
50	9	wurzer-helmut.in.	USPAT; US-PGPUB; EPO; JPO; DERWENT; IBM_TDB	2002/03/08 15:41